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Low Temperature Properties of Ta_xN SNS Junctions

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Motivation:

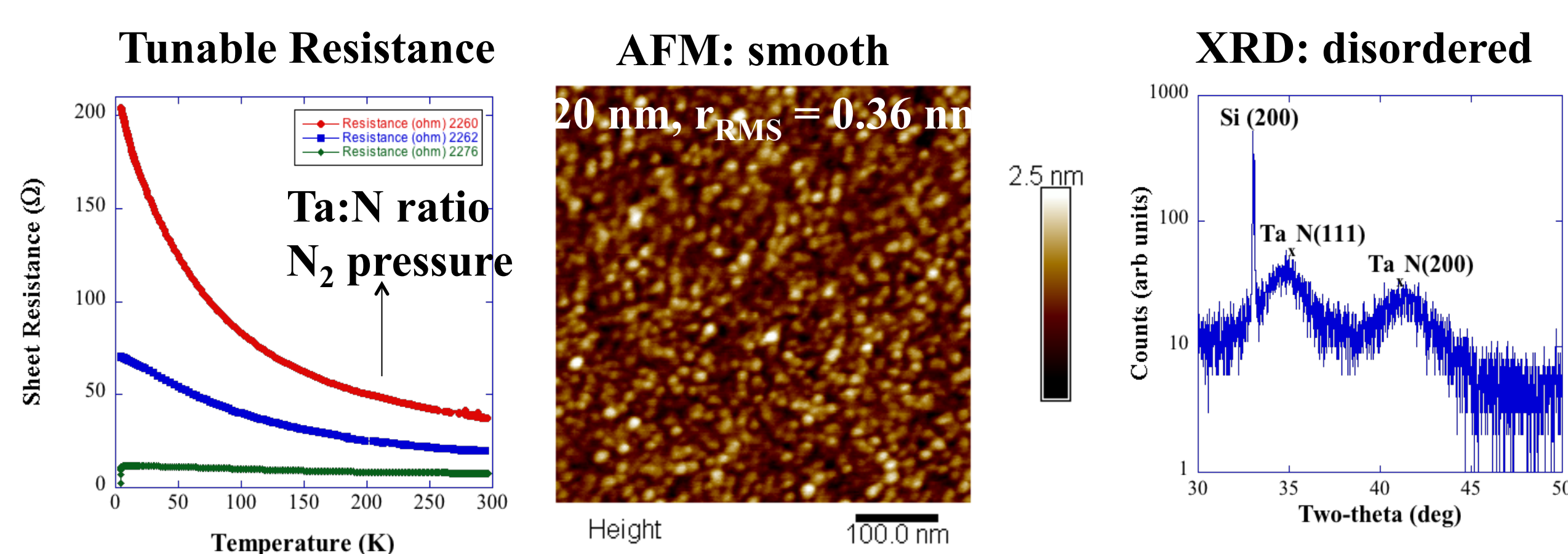
Can Ta_xN offer advantages over AlO_x barriers?

- Thermal stability – can use optimized dielectric, potential for 3D scaling
- Barrier properties can be tuned – self shunting, may be less susceptible to electronic defects
- High quality films and JJs previously demonstrated on crystalline substrates and/or with high temperature growth [1-14]

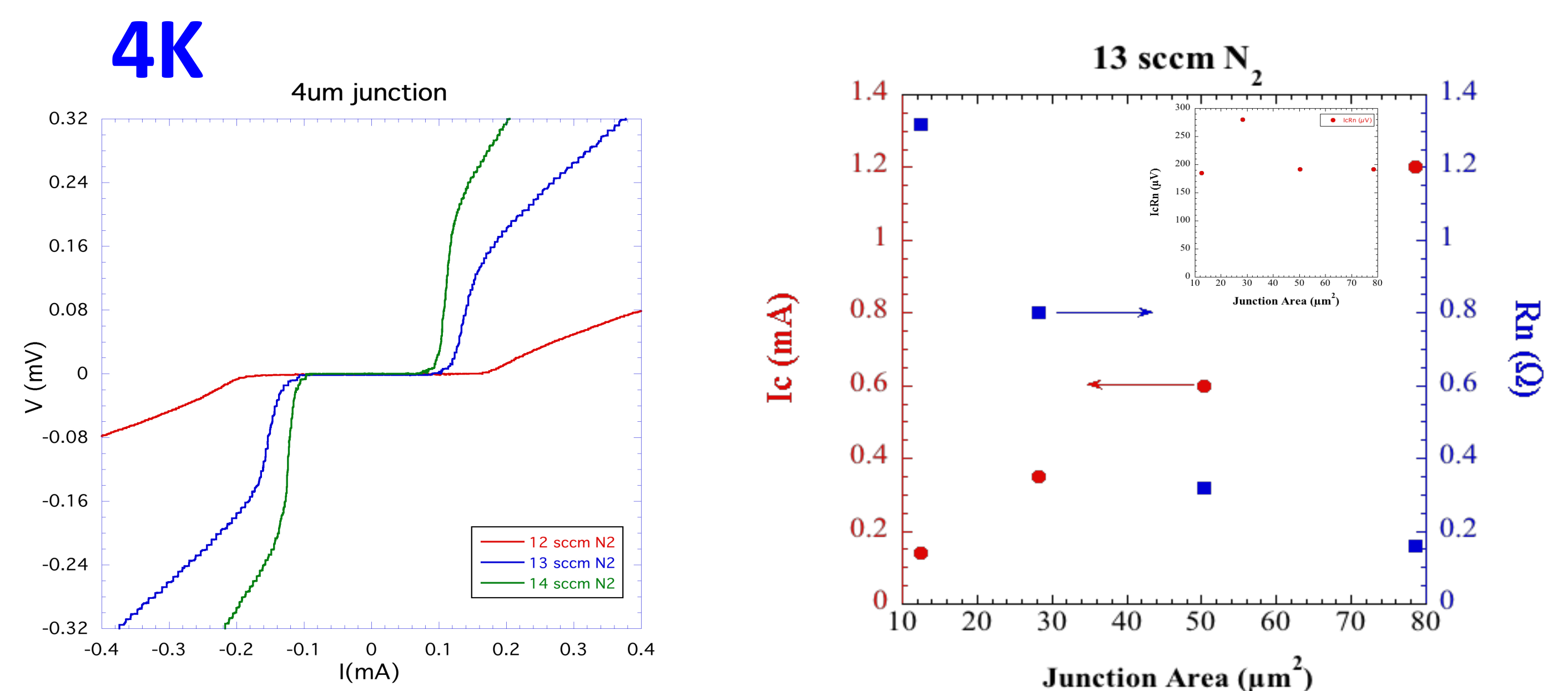
Approach:

Explore Nb/Ta_xN/Nb JJs grown at *ambient temperature* on *SiO₂/Si* substrates (for future scaling)
see M. D. Henry poster!

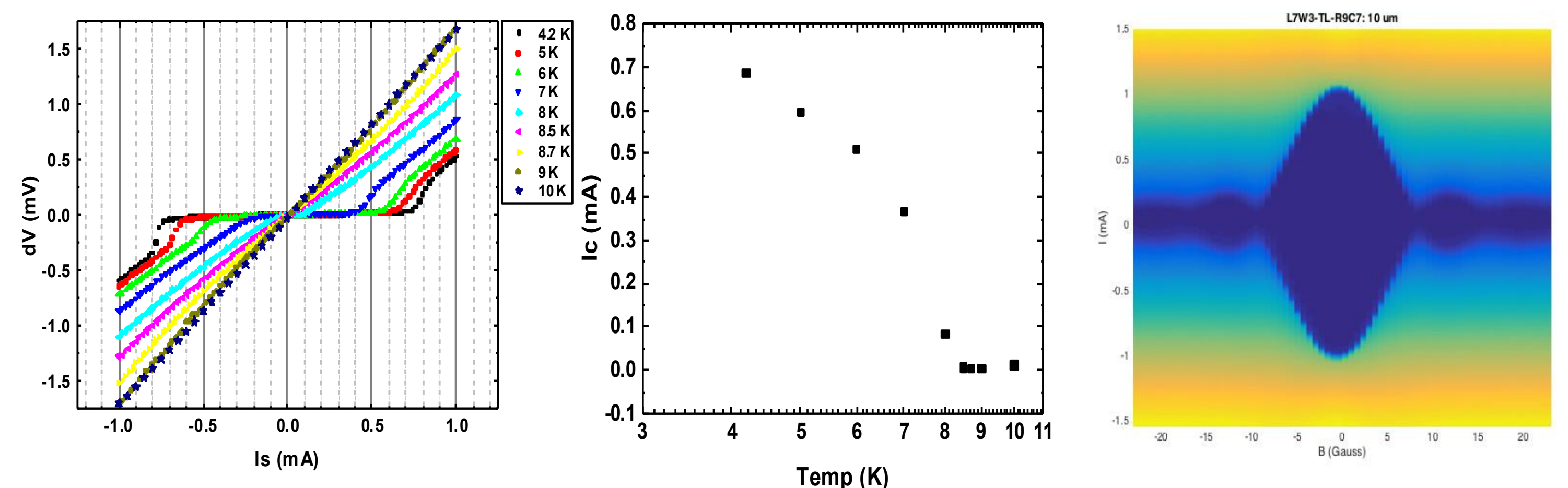
Single Ta_xN films on SiO₂/Si substrates are smooth, single phase and have tunable electronic properties



Low T Junction Properties:



Temperature, Field Dependence



- I_cR_n products depend on both barrier thickness and N content
- I_cR_n products up to 0.35 mV have been achieved

Future Directions:

- Improved statistics to better understand dependence of properties on N content and thickness in order to increase I_cR_n – correlate with 300K resistance measurements
- Explore multiple JJ layers, processing temperature stability

1) Westra, K.L., J. Vac. Sci. Tech. A, 8, 1288, (1990); 2) Treece, R. E. et. al., Appl. Phys. Lett. 65 (22), 2860, (1994); 3) Wang, Z. et. al., Supercond. Sci. Technol., 12, 868, (1999); 4) Kaul, A. B. et. al., Appl. Phys. Lett., 78, 99, (2001); 5) Kaul, A. B. et. al., IEEE Trans. Appl. Supercond. 11, 88, (2001); 6) Terai, H. et. al., IEEE Trans. Appl. Supercond., 11, 525–528, (2001); 7) Yu, L. et. al., Phys. Rev. B, 65, 245110, (2002); 8) Setzu, R. et. al., J. Phys. Conf. Ser. 97, 012077 (2008); 9) Nevala, M. R., et. al., IEEE Trans. Appl. Supercond. 19, 253, (2009); 10) Villegier, J.-C., et. al., IEEE Trans. Appl. Supercond. 19, 3375, (2009); 11) Villegier, J.-C., et. al., IEEE Trans. Appl. Supercond. 21, 102, (2011); 12) Yamamori, H. et al., IEICE Trans. Electron., E95-C, 329, (2012); 13) Makise, K. et. al., IEEE Trans. Appl. Supercond. 23, 1100804, (2013); 14) Akaike, H. et. al., IEEE Trans. Appl. Supercond. 23, 1101306, (2013).



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